

## **Amendments to the Claims:**

*This listing of claims will replace all prior versions, and listings, of claims in the application:*

Claims 1 - 4. (Cancelled)

5. (Previously Presented) A process for removing AlCl<sub>3</sub> from a compound mixture comprising organochlorosilanes and having an AlCl<sub>3</sub> content of > 200 ppm based on the weight of organochlorosilanes, comprising diluting the compound mixture with diluent comprising organochlorosilanes or mixtures of chloromethane and organochlorosilanes to form a product stream with < 15 weight percent solids at a simultaneous concentration of < 25 weight percent of components having a boiling point > 71°C at 1013 hPa, and separating this product stream in an evaporator unit at a temperature < 165°C into volatile compounds and AlCl<sub>3</sub>-containing solid.

6. (Previously Presented) The process of claim 5, wherein the compound mixture is derived from the direct synthesis of alkylchlorosilanes, or from the AlCl<sub>3</sub>-catalysed high boiler cleavage of by-products of the direct synthesis.

7. (Currently Amended) The process of claim 5, wherein the organochlorosilanes are alkylchlorosilanes of the formula R<sub>a</sub>H<sub>b</sub>SiCl<sub>4-a-b</sub> in which a is 1, 2, or 3 [[or 4]], b is 0, 1 or 2, [[and]] R is a methyl, ethyl, butyl or propyl radical, and at least one chlorine is present.

8. (Currently Amended) The process of claim 6, wherein the organochlorosilanes are alkylchlorosilanes of the formula R<sub>a</sub>H<sub>b</sub>SiCl<sub>4-a-b</sub> in which a is 1, 2, or 3 [[or 4]], b is 0, 1 or 2, [[and]] R is a methyl, ethyl, butyl or propyl radical, and at least one chlorine is present.

9. (Previously Presented) The process of claim 5, wherein the evaporator unit used is a spray evaporator, thin-layer evaporator, or thin-film evaporator.

10. (Previously Presented) The process of claim 6, wherein the evaporator unit used is a spray evaporator, thin-layer evaporator, or thin-film evaporator.

11. (Previously Presented) The process of claim 8, wherein the evaporator unit used is a spray evaporator, thin-layer evaporator, or thin-film evaporator.